

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"2000255579"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 08:35
L3	6	(toppan printing).as. and plasma CVD and (organic silicon or organosilicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 08:41
L7	0	(toppan printing).as. and plasma CVD and (flow with ratio)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:09
L8	242	(plasma CVD or PECVD or (plasma with chemical vapor deposition)) and (organosilicon or organic silicon or HDMSO or hexamethyltrisiloxane) and (flow with ratio)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:10
L9	8	(plasma CVD or PECVD or (plasma with chemical vapor deposition)) and (organosilicon or organic silicon or HDMSO or hexamethyltrisiloxane) and (flow with ratio with decreas \$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:10
L10	744	(ito or yamamoto or takeda or shirai or iijima or kakemura).in. and plasma CVD and (organic silicon or organosilicon or silicon oxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:17
L11	27	10 and (plastic container or bottle)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:18
L13	18	427/237.ccls. and (organosilicon or HMDSO or TEOS or hexamethyldisiloxane) and (plasma CVD or PECVD or (plasma with chemical vapor deposition))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:36

L14	91	(toppan printing).as. and plasma CVD	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:44
L15	8	14 and plastic container	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:44
L16	2	("6152071").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:48
L17	1	"8316214"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:53
L18	2	"08316214"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:53
L20	602	(plasma CVD or (plasma with chemical vapor deposition) or PECVD) and (match\$3 same reflect\$3 same power same (reduc\$3 or decreas\$3 or control\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:56
L21	304	(plasma CVD or (plasma with chemical vapor deposition) or PECVD) and (match\$3 same reflected power with (reduc\$3 or decreas\$3 or control\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:57
L22	211	21 and (silicon oxide or organosilicon or organic silicon or HMDSO or TEOS)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 09:57
L23	493	(plasma CVD or (plasma with chemical vapor deposition) or PECVD) and (organic silicon or organosilicon or silicon oxide or HMDSO) and (plastic container or bottle)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 10:04
L24	1	23 and ((reduc\$3 with reflect\$3 power) same match\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 10:04

L25	138	(plasma CVD or (plasma with chemical vapor deposition) or PECVD) and (organic silicon or organosilicon or silicon oxide or HMDSO) and ((reduc\$3 with reflect\$3 power) same match \$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 10:05
L26	182	23 and ((control\$3 or decreas \$3 or vary\$3) with (flow or ratio or concentration))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 10:06
L27	32	plasma CVD and (flow amount ratio)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 10:20
L28	15	("5904952").URPN.	USPAT	ADJ	OFF	2008/08/28 10:24
L29	1	"0741196"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 11:04
L30	12	"741196"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 11:04
L31	5	(reflect\$3 power with frequency same match\$3) and (plasma CVD) and (HMDSO or hexamethyldisiloxane or organosilicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 12:46
L32	5	(reflect\$3 power with (reduc\$3 or lower\$3 or control\$3)) and (plasma CVD) and (HMDSO or hexamethyldisiloxane or organosilicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 12:49
L33	12	(reflect\$3 power with (reduc\$3 or lower\$3 or control\$3)) and plasma and (HMDSO or hexamethyldisiloxane or organosilicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2008/08/28 12:49

8/28/2008 1:00:40 PM

C:\Documents and Settings\Ewhitehead.USPTO\My Documents\EAST\Workspaces\10  
\10529362.hydrogen alpha rays.wsp